

ABSTRACT

SUBSTRATE WITH MULTILAYER REFLECTIVE FILM, REFLECTIVE MASK
BLANK, REFLECTIVE MASK, AND METHOD OF MANUFACTURING
5 SEMICONDUCTOR DEVICE

Provided is a substrate with multilayer reflective film (110) used to manufacture a reflective mask (200) having a multilayer reflective film (5) having high reflectance with respect to exposure light and little film stress. The substrate with multilayer
10 reflective film is provided with a multilayer reflective film for reflecting exposure light, the substrate with multilayer reflective film comprising a multilayer film obtained by alternately laminating low refractive index layers and high refractive index layers on a substrate (1), and the multilayer reflective film contains krypton (Kr).

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Fig. 3